

FORMING PLANARIZED SEMICONDUCTOR STRUCTURES

Abstract of the Disclosure

A planarized surface may be formed by initially forming an aperture through an insulating layer. The insulating layer and its aperture may be conformally coated
5 with a conductive material that ultimately acts as a planarization stop. The conductive material may then be covered with another insulator that fills the remainder of the aperture. Thereafter, the structure may be planarized
10 down to the conductive layer that acts as a planarization stop.